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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Chen et al.

Serial No.: 10/032,284

Filed: December 21, 2001

For: Gas Delivery Apparatus and
Method for Atomic Layer
Deposition

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Group Art Unit: Unknown

Examiner: Unknown

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Assistant Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

CERTIFICATE OF MAILING 37 C.F.R. 1.8	
I hereby certify that this correspondence is being deposited on February 7, 2002, with the U. S. Postal Service as First Class Mail in an envelope addressed to: Assistant Commissioner for Patents, Washington, D.C. 20231.	
February 7, 2002 Date	 Signature

PRELIMINARY AMENDMENT

Prior to examination of the above referenced application, Applicants request that
the application be amended as follows:

IN THE SPECIFICATION:

Please replace the paragraph [0001] with the following paragraph [0001]:

[0001] This application claims benefit of United States provisional Patent
Application Serial Number 10/032,284, entitled "METHOD AND APPARATUS FOR
ALD DEPOSITION," filed October 26, 2001, which is herein incorporated by reference.

IN THE DRAWINGS:

Applicants submit corrections to the drawings to rectify errors noted subsequent
to filing the application. Applicants have submitted the corrections marked in red on the
attached copy of the original drawing of Figure 1 filed in the application. The
corrections conform the drawings to the written description of the invention without